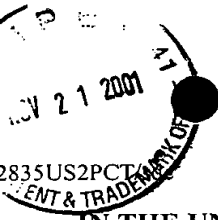


Docket No.

212835US2PCT



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Michio SATO, et al.

SERIAL NO: 09/926,041

GAU: 1734

FILED: August 20, 2001

EXAMINER:

FOR: COMPONENTS FOR VACUUM DEPOSITION APPARATUS AND VACUUM DEPOSITION APPARATUS
THEREWITH, AND TARGET APPARATUS

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#3

INFORMATION DISCLOSURE/RELATED CASE STATEMENT UNDER 37 CFR 1.97

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

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TC 1700

SIR:

Applicant(s) wish to disclose the following information.

REFERENCES

- ☒ The applicant(s) wish to make of record the references, some of which are cited in the attached International Search Report listed on the attached form PTO-1449. Copies of reference(s) AH through AK, have been received by the U.S. PCT Receiving Office from the International Bureau as acknowledged in the Notification of Acceptance.
- ☐ A check is attached in the amount required under 37 CFR §1.17(p).

RELATED CASES

- ☐ Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s) is attached along with PTO 1449.
- ☐ A check is attached in the amount required under 37 CFR §1.17(p).

CERTIFICATION

- ☐ Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- ☐ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

DEPOSIT ACCOUNT

- ☒ Please charge any additional fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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STATEMENT OF RELEVANCE

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Reference AL (JP 4-268065) on Form 1449:

A deposition preventive plate and a shutter are formed of a member low in coefficient of thermal expansion (from 3.5 to 7.5×10^{-6}) and high in mechanical strength (Yong's modulus: from 1.7 to 3.3×10^{11} N/m²), and material (Al) high in film adherence to a sputtered film is spray deposited.

Reference AM (JP 6-196437) on Form 1449:

An apparatus for depositing a thin film of titanium or titanium compound in which as a constituent of a reaction chamber, a component formed of titanium or titanium compound or a component on the surface thereof titanium compound is spray deposited is used.

Reference AN (JP 8-176816) on Form 1449:

A method for surface treating a deposition preventive plate for film forming apparatus in which to the deposition preventive plate, by the use of a mask having an opening, desired metal is spray deposited through the opening.

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STATEMENT OF RELEVANCY

Reference AO (JP 8-277461)) on Form 1449:

In a sputtering apparatus for obtaining a dielectric film on a substrate by the use of a ceramic target, a surface thereon plasma of a device component is present is coated by an insulator (Al_2O_3 , TiO_2 , SiO_2 , MgO , B_4C).

Reference AP (JP 9-87834) on Form 1449:

A sputtering apparatus in which insulating material is disposed between a cathode unit and a cathode case.

Reference AQ (JP 9-275082) on Form 1449:

In a reverse sputtering apparatus in which a substance adhered on a surface of an object being treated is removed, an inside surface of a reaction chamber is covered by spray deposit of high purity metal (Al of 99.7 % or more in purity).

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STATEMENT OF RELEVANCY

Reference AR (JP 10-204604) on Form 1449:

A member for thin film deposition apparatus in which a surface of spray deposit coating a metal substrate is formed in lattice of uneven height.

References AS through AV on Form 1449:

These references are discussed in the specification.